## **Listing of Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (previously presented) A deposit monitoring apparatus located above ground level comprising:

an acoustic device for operating in a longitudinal mode and in a resonance mode in a frequency range of 10 kHz to 250 kHz, the device including a monitoring surface directly exposed to fluids prone to causing deposition of material, wherein the deposition of the material on the monitoring surface is monitored by measuring a change in resonance frequency of the acoustic device; and

a power supply for supplying said acoustic device with electrical energy.

- 2. (cancelled)
- 3. (previously presented) The apparatus of claim 1, wherein the acoustic device further comprises a transducer, and a focusing element coupled to the transducer.
- 4. (original) The apparatus of claim 3, wherein the focussing element is an acoustic horn.
- 5. (original) The apparatus of claim 1, wherein the resonance frequency of the acoustic device is in the range of 10 kHz to 150 kHz.
- 6. (original) The apparatus of claim 5 wherein the resonance frequency of the acoustic device is in the range of 50 kHz to 100 kHz.
- 7. (original) The apparatus of claim 1 wherein the fluids are primarily fluids produced by a hydrocarbon wellbore.

- 8. (original) The apparatus of claim 1, wherein the monitoring surface is located on or near one of the following devices switches, valves, sleeves, mandrels, risers, subsea pipelines, surface separators and sensors located on surface facilities.
- 9. (previously presented) The apparatus of claim 1 further comprising a deposit removal system for at least partially removing the deposition from the monitoring surface, the deposit removal system being in a control loop with said deposit monitoring apparatus.
- 10. (original) The apparatus of claim 9, wherein the deposit removal system includes a deposition inhibiting or removing chemical agent.
- 11. (original) The apparatus of claim 9, wherein the deposit removal system uses the acoustic device to exert a physical force onto the deposited material.
- 12. (previously amended) The apparatus of claim 9, wherein the deposition removal system is near a sensor having a surface exposed to the fluids and the deposition removal system removes deposits from said exposed surface.
- 13. (original) The apparatus of claim 12, wherein the sensor is selected from a group comprising optical sensors, electro-chemical sensors, or acoustic sensors.
- 14. (previously presented) The apparatus of claim 12, wherein the exposed sensor surface is selected from a group comprising optical windows, membranes, or sensitive areas of acoustic sensors.
- 15. (currently amended) The apparatus of claim 1, wherein the sensor includes comprising an additional sensing system to analyze material deposited on the monitoring surface.
  - 16. (cancelled)
  - 17. (cancelled)

- 18. (cancelled)
- 19. (cancelled)
- 20. (currently amended) The apparatus of claim 19 A monitoring apparatus located above ground level comprising:

a monitor to measure characteristics of fluids the monitor having a monitoring surface that is directly exposed to the fluids;

a deposit removal system including an acoustic device for exerting a physical force on the monitoring surface to at least partially remove the deposition from the monitoring surface, the deposit removal system being in a control loop with said deposit monitor; and

a power supply for supplying said acoustic device with electrical energy, wherein the monitor further uses said acoustic device, said acoustic device to be operated in a resonance mode, and wherein the monitor measures deposition of the material on the monitoring surface by measuring a change in resonance frequency of the acoustic device and wherein the acoustic device operates in a longitudinal mode.

- 21. (currently amended) The apparatus of claim 1920, wherein the acoustic device further comprises a transducer, and a focusing element coupled to the transducer.
- 22. (currently amended) The apparatus of claim 1920, wherein the resonance frequency of the acoustic device is in the range of 10 kHz to 150 kHz.
  - 23. (cancelled)
  - 24. (cancelled)
  - 25. (cancelled)

- 26. (currently amended) The apparatus of claim 1620, wherein the monitor is selected from a group comprising optical sensors, electro-chemical sensors, or acoustic sensors separate from the force exerting acoustic device.
- 27. (currently amended) The apparatus of claim 1620, wherein the monitor is a gamma ray density measurement system.
- 28. (previously presented) The apparatus of claim 27 wherein the monitoring surface is a nuclear window.
- 29. (currently amended) The apparatus of claim 1620, wherein the monitor is an optical fluid analyzer.
- 30. (previously presented) The apparatus of claim 29 wherein the monitoring surface includes and optical window.
- 31. (currently amended) The apparatus of claim <u>1620</u>, wherein the monitor is used to measure activity of an ionic species contained in the wellbore fluid.
- 32. (previously presented) The apparatus of claim 31 wherein the monitoring surface is a membrane of an ion selective electrode.
- 33. (currently amended) The apparatus of claim 1620, wherein the monitoring surface is a separation membrane.
  - 34. (cancelled)
- 35. (currently amended) The apparatus of claim 34 A deposit monitoring apparatus located above ground level comprising:

an acoustic device to operate in a resonance mode including a monitoring surface directly exposed to fluids produced by a hydrocarbon wellbore, wherein the deposition of material on the monitoring surface is monitored by measuring a change

Attorney Docket No. 57.0410 US PCT

Appl. No. 10/088,723 Amdt. After Final dated 20 October 2004 Reply to Final Office Action of 25 August 2004

Page 6 of 7

in resonance frequency of the acoustic device, and wherein by measuring said change in resonance frequency of the acoustic device a thickness of deposited material of 600 microns can be distinguished from a thickness of deposited material of 1050 microns;

<u>and</u>

a power supply for supplying said acoustic device with electrical energy, wherein the

acoustic device operates in a longitudinal mode.

36. (previously presented) The apparatus of claim 35, wherein the acoustic device

further comprises a transducer, and an acoustic horn coupled to the transducer.

37. (currently amended) The apparatus of claim 3435, wherein the resonance

frequency of the acoustic device is in the range of 10 kHz to 150 kHz.

38. (cancelled)

39. (cancelled)

40. (cancelled)